

LAW OFFICES  
**SUGHRUE, MION, ZINN, MACPEAK & SEAS, PLLC**

2100 PENNSYLVANIA AVENUE, N.W.  
WASHINGTON, DC 20037-3213  
TELEPHONE (202) 293-7060  
FACSIMILE (202) 293-7860  
www.sughrue.com

03/06/00  
JC535 U.S. PTO  
**BOX PATENT APPLICATION**  
Assistant Commissioner for Patents  
Washington, D.C. 20231

03/06/00  
JC535 U.S. PTO  
09/519847

March 6, 2000

Re: Application of **Pierre RIPOCHE, Alain DROUART, and Benoit GOUEZ**

**METHOD OF FABRICATING AN OPTICAL FIBER PREFORM INCLUDING  
OUTSIDE DEPOSITION OF SILICA, POSSIBLY DOPED SILICA**  
Our Ref. Q58134

Dear Sir:

Attached hereto is the application identified above including 10 sheets of the specification, claims and abstract, 3 sheets of formal drawings, executed Assignment and PTO 1595 form, and executed Declaration and Power of Attorney. Also enclosed is the Information Disclosure Statement.

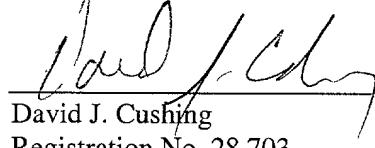
The Government filing fee is calculated as follows:

Total claims	3	-	20	=	0	x	\$18.00	=	\$0.00
Independent claims	1	-	3	=	0	x	\$78.00	=	\$0.00
Base Fee									\$690.00
<b>TOTAL FILING FEE</b>									
Recordation of Assignment									
<b>TOTAL FEE</b>									
\$690.00									
\$40.00									
<b>\$730.00</b>									

Checks for the statutory filing fee of \$690.00 and Assignment recordation fee of \$40.00 are attached. You are also directed and authorized to charge or credit any difference or overpayment to Deposit Account No. 19-4880. The Commissioner is hereby authorized to charge any fees under 37 C.F.R. §§ 1.16 and 1.17 and any petitions for extension of time under 37 C.F.R. § 1.136 which may be required during the entire pendency of the application to Deposit Account No. 19-4880. A duplicate copy of this transmittal letter is attached.

Priority is claimed from March 08, 1999 based on French Application No. 9902815. The priority document is enclosed herewith.

Respectfully submitted,  
**SUGHRUE, MION, ZINN,  
MACPEAK & SEAS, PLLC**  
Attorneys for Applicant

By:   
David J. Cushing  
Registration No. 28,703

ABSTRACT OF THE DISCLOSURE

A method of fabricating an optical fiber preform is disclosed which includes a step of outside deposition of silica possibly doped with at least one dopant by 5 injecting at least one substance in the form of silica or a precursor of silica in the vicinity of a heating area created by a heating system during at least one pass of an injector system and the heating system along a longitudinal axis of the preform during which the relative positions of the injector and heating systems are adjusted so that silica is deposited in the heated area regardless of the position of the heating 10 system.

METHOD OF FABRICATING AN OPTICAL FIBER PREFORM INCLUDING OUTSIDE  
DEPOSITION OF SILICA, POSSIBLY DOPED SILICA

BACKGROUND OF THE INVENTION

Field of the invention

5       The present invention relates to a method of fabricating an optical fiber preform including a step of outside deposition of silica possibly doped with at least one dopant by injecting at least one substance in the form of silica or a precursor of silica in the vicinity of a heating area created by heating means during at least one pass of injector means and the heating means along a longitudinal axis of the  
10      preform. It also relates to a preform obtained by the above method and an optical fiber fabricated by drawing the above preform.

Description of the prior art

Using an outside lateral deposition technique such as the plasma surfacing technique to fabricate a preform, which is subsequently drawn to fabricate an optical  
15      fiber, from another preform referred to as the primary preform, which includes the optical guide part of the optical fiber obtained from the preform, is known in the art and described in patent application EP 0 450 465 A1, for example.

The optogeometrical characteristics of an optical fiber determine transmission characteristics. They include the geometry of the fiber, in particular the  
20      surfaces of the various concentric parts of the fiber when seen in cross section, and the optical characteristics of these various parts. These optogeometrical characteristics are derived from those of the preform from which the optical fiber is fabricated.

Patent application EP 0 719 738 A1 describes a method of obtaining optical  
25      fiber preforms using a plasma surfacing process, i.e. an outside deposition process using a plasma torch as the heating means, in which method silica, possibly doped silica, and generally in the form of grains of silica, is injected into the torch and at least one plasma surfacing pass is modulated to improve the optogeometrical properties of the preform. The surfacing pass which is modulated is one of the final  
30      surfacing passes; during unmodulated passes the thickness of the surfacing layer deposited is substantially constant along the usable part of the preform. The surfacing process is modulated principally by controlled axial modification of at least one plasma surfacing parameter, preferably the flowrate of the surfacing grains. The axial modification process includes evaluating axial diameter errors of the preform and axially modifying the parameter in a direction such that the modulated surfacing

pass reduces the axial diameter errors. In other words, the surfacing pass is modulated according to axial diameter errors previously determined and adds to - or subtracts from - the diameter of the preform so that the errors are reduced - or even eliminated - after the surfacing pass.

5 However, in patent application EP 0 719 738 A1 the outside deposition yield is not optimized: the injector means, in this instance for injecting grains, are permanently positioned relative to the plasma torch throughout the duration of outside deposition. The heating means (the plasma torch) do not operate symmetrically about their axis on the reactive gases or particles leaving the injector means, principally because of the vortex flow of the plasma gases in the torch and at the outlet from the torch. Consequently, in an outside deposition process alternating deposition passes in opposite directions, the position of the injector means in the prior art typically represents a compromise. Its position is between an optimum position in one direction of translatory movement of the preform and an optimum position in the 10 other direction of translatory movement of the preform. Consequently, the outside deposit is not optimized, in particular in terms of the yield; the reactive gases or grains leaving the injector means and which have not reacted in the heating area of the heating means are purely and simply eliminated without having been able to react.

15 20 With a process of the above kind it is also difficult to deposit dopants such as fluorine with some rates of incorporation into the preform. The position of the injector means can make it impossible to obtain correct doped reactant deposition reaction kinetics, principally in terms of temperature and the distance to be traveled by the reactants leaving the injector means if the reactants are gases. Fluorine, for example, is too reactive and, instead of silica and fluorinated substance being deposited on the 25 preform, an unwanted compound  $\text{SiF}_4$  is formed which is not incorporated into the preform. In the worst case scenario not only is the fluorine dopant not incorporated into the preform but it also impedes or even prevents the deposition of silica on the preform.

30 35 In the context of the outside vapor deposit (OVD) technology, in which an outside deposit of possibly doped silica is produced by a succession of outside deposit passes of soot in the presence of the heating means, which are generally in the form of an oxyhydride torch, vitrification occurring after such deposition, generally in an oven, the problem also arises of optimizing the outside deposit, in addition to the problem of depositing some dopants under some conditions. It is also feasible to

form an OVD deposit by using a plasma torch as the heating means instead of an oxyhydride torch.

The method of the invention aims principally to increase the deposition yield of the outside deposit process by optimizing the position of the injector means relative 5 to the heating means. It also aims to enable simultaneous deposition of dopants and silica under good conditions.

#### SUMMARY OF THE INVENTION

The invention provides a method of fabricating an optical fiber preform including a step of outside deposition of silica possibly doped with at least one 10 dopant by injecting at least one substance in the form of silica or a precursor of silica in the vicinity of a heating area created by heating means during at least one pass of injector means and the heating means along a longitudinal axis of the preform during which the relative positions of the injector means and the heating means are adjusted so that the silica is deposited in the heated area regardless of the position of 15 the heating means.

In the case of direct vitrification, where possibly doped silica soot is deposited and the soot is simultaneously vitrified, it is very important to obtain a good quality preform, and in particular for no bubbles to be incorporated in the preform. While significantly improving the silica deposition yield, generally by 20% to 30% 20 compared to a compromise position of the injector means, the method of the invention has the advantage of producing a high-quality deposit essentially free of bubbles.

The method according to the invention also has the advantage, principally in the case of injecting gaseous reactants, of obtaining some levels of dopants in the 25 silica deposited by the surfacing process which a standard position of the injector means cannot achieve well, if at all.

The adjustment is advantageously carried out at each change of pass.

The method of the invention therefore has the advantage, principally in the case of depositing grains in both surfacing pass directions, at constant deposit 30 quality, of increasing the rate of deposition of the particles deposited on the preform in a lateral surfacing layer, compared to the process in which the injector means are fixed at a particular position throughout the surfacing process.

In one embodiment of the invention the heating means have a main axis in a plane substantially perpendicular to the longitudinal axis of the preform, the 35 injector means have a main axis at a fixed angle to the main axis of the heating

means in a plane substantially perpendicular to the longitudinal axis of the preform and the injector means and the heating means move relative to each other in a direction parallel to the longitudinal axis of the preform.

In this configuration the orientations of the principal axes of the injector  
5 means and the heating means are conventional for the process of outside deposition of possibly doped silica, principally in the case of plasma surfacing, and the method of the invention can easily be adapted to existing systems. The relative movement of the injector means and the heating means is performed with their axes remaining in a plane perpendicular to the longitudinal axis of the preform and with a constant angle  
10 between the axes. It is therefore easy to automate the relative position of the injector means and the heating means on existing systems.

The heating means according to the invention are generally in the form of a plasma torch, principally in the case of the plasma technology, but also in the case of the OVD technology.  
15

If there are at least two injectors, the foregoing remarks apply to each of the injectors. In this case the injectors are generally situated in a common plane substantially perpendicular to the longitudinal axis of the preform.

In the case of a deposit of undoped silica, whether deposited by injecting grains or by injecting reactive gases, the positioning of the injector means, which in  
20 this case is principally dependent on the direction of translatory movement of the preform relative to the heating means, is generally continuously adjusted as the preform is fabricated. This can be effected by measuring the diameter continuously, as described in patent application EP 0 719 738 A1 in the situation where the heating means are in the form of a plasma torch. The position of the injector means  
25 according to the invention can also be evaluated and adjusted by calibration on preforms used as test preforms.

In the case of depositing doped silica, usually by injecting reactive gases, the position of the injector means is generally determined by calibration on preforms used as test preforms. In this case their position is principally dependent on the  
30 direction of movement of the preform in translation relative to the heating means and the doping required at a given diameter of the preform, depending on the required refractive index profile. Calibration using one or two test preforms must therefore evaluate different positions of the injector means relative to the heating means as a function of the speed of translatory movement for a given refractive index profile.

35 The invention will be better understood and other features and advantages

of the invention will become apparent on reading the following description which is given by way of non-limiting example with reference to figures 1 to 5.

#### BRIEF DESCRIPTION OF THE DRAWINGS

Figure 1 is a highly diagrammatic representation of a plasma surfacing system in which the method of the invention can be implemented.

Figure 2 is a diagrammatic view taken along the line I-I in figure 1 of the various components of the system shown in figure 1 in a prior art position which represents a compromise and in the case of leftward translatory movement of the preform 3 relative to the nozzle 5 and the torch 4.

Figure 3 is a diagrammatic view taken along the line I-I in figure 1 of the various components of the system shown in figure 1 in a prior art position which represents a compromise and in the case of rightward translatory movement of the preform 3 relative to the nozzle 5 and the torch 4. The difference compared to figure 2 is the direction of translatory movement.

Figure 4 is a diagrammatic view taken along the line I-I in figure 1 of the components of the system shown in figure 1 in a position optimized in accordance with the invention in the case of leftward translation of the preform 3 relative to the nozzle 5 and the torch 4.

Figure 5 is a diagrammatic view taken along the line I-I in figure 1 of the components of the system shown in figure 1 in a position optimized in accordance with the invention in the case of rightward translation of the preform 3 relative to the nozzle 5 and the torch 4. The difference compared to figure 4 is the direction of translatory movement.

#### DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENT

Figure 1 is a highly diagrammatic representation of a plasma surfacing system including an enclosure 1 which has a transparent window 2, a preform 3 which is seen end on and onto which are directed a plasma torch 4 which constitutes the heating means in accordance with the invention and a nozzle 5 feeding surfacing grains which has an orifice 5a and constitutes the injector means according to the invention. Outside the enclosure 1 is a CCD video camera 6 behind the window 2 and pointing toward the preform 3, which has a longitudinal axis X. It provides a measurement of the diameter of the preform at the location at which it points in the form of a value transmitted by a link 7 to a device 8 controlling the surfacing process. The device 8 receives over a multiple link 9 other information on surfacing process conditions. Under the control of an internal program controlling the surfacing

process, and for a constant flowrate of the grains, the device 8 provides on an output link 10 feeding a control device 11 a command which positions the nozzle 5 relative to the torch 4 and the preform 3 by moving the nozzle 5 along an axis parallel to the longitudinal axis X of the preform 3. The reference value is that for which the nozzle  
5 and the torch 4 are in a common plane substantially perpendicular to the axis of the preform. The device 8 also supplies on a multiple output link 12 other command values determining other aspects of the control process.

All the components of the system shown in figure 1 are well known to the skilled person. Other components which are not shown are equally well known.  
10 Thus means for supporting the preform 3 with rotary and translatory drive, a carriage supporting the plasma torch 4 and the nozzle 5 with translatory drive parallel to the longitudinal axis of the preform 3, and means for evaluating the angular position of the preform 3 and the longitudinal position of the carriage are described in European patent application EP 0 440 130 A1 , for example. According to the invention, the  
15 carriage supporting the nozzle 5 and the torch 4 also includes internal means for supporting the nozzle 5 with translatory drive for positioning the nozzle 5 relative to the torch 4. In a manner that is well known in the art, all these means are used to move the preform 3 away from the torch 4 as the preform 3 grows larger. The camera 6 is pointed at successive locations of the preform 3 along a measurement path by means which could take the form of a second carriage, movement of which is  
20 coupled to that of the first carriage, also as in the prior art.

The plasma surfacing is effected by alternating passes from right to left and from left to right during which the plasma torch 4 and the nozzle 5 are swept along the length of the preform 3. In accordance with the invention, the position of the nozzle 5 relative to the torch 4 is preferably changed at each change in the direction of translatory movement of the torch 4 relative to the preform 3 at the end of a pass. In figures 2 and 3, which are described later, the position of the nozzle 5 relative to the torch 4 in the prior art is typically fixed for every pass and therefore exactly the same regardless of the direction of translatory movement of the preform 3 relative to  
25 the torch 4. In figures 4 and 5, which are described later, the position of the nozzle 5 in accordance with the invention is different for each direction of translatory movement of the preform 3 relative to the torch 4 and is modified on each change of direction at the end of a pass. The position is preferably the same for a given direction of translatory movement, but can also vary during the process, being slaved  
30 to the diameter of the preform.  
35

All of the control process is optimized to obtain a high yield in terms of the quantity of silica deposited at a given speed of translatory movement and for a given refractive index profile of the surfacing. The camera 6 simultaneously performs a measurement pass providing successive values of the diameter of the preform 3 throughout its length.

Figure 2 is a diagrammatic view of the various components of the system shown in figure 1 in a prior art position which represents a compromise in the case of leftward translatory movement (arrow F) of the preform 3 relative to the nozzle 5 and the torch 4. The arrow F indicates the direction of translatory movement of the preform 3. The nozzle 5 is symbolized by its orifice 5a. A cone 14 of deposition of reactive gases or particles leaving the nozzle 5 and a plasma 15 issuing from the plasma torch 4 are shown. The cone 14 overlaps a hot area ABCD of the preform 3 and there is a cold area BCE of said cone 14, shown shaded in figure 2. As previously explained, deposition by this process in the cold area has the drawback of reducing the yield of the deposit, or even of preventing it altogether in the case of some dopants.

Figure 3 is a diagrammatic representation of the components of the system shown in figure 1 in a prior art position which represents a compromise in the case of rightward translation (arrow F') of the preform 3 relative to the nozzle 5 and the torch 4. The arrow F' indicates the direction of translatory movement of the torch. As in figure 2, the cone 14 of deposition of the reactive gases or particles leaving the nozzle 5 via the orifice 5a and the plasma 15 and the hot area ABCD of the preform 3 are shown. The cone 14 overlaps the hot area ABCD and there is a cold area BCE.

Figure 4 is a diagrammatic representation of the components of the system shown in figure 1 in a position optimized in accordance with the invention in the case of leftward translatory movement of the preform 3 relative to the nozzle 5 and the torch 4. Downstream of the torch refers to the part of the torch which has already undergone deposition during the pass shown. The axis of the nozzle 5 is at a distance d from the axis of the torch 4, on its downstream side relative to the direction of translatory movement of the preform 3 relative to the torch 4. Consequently the cone 14 of deposition of the gases or particles leaving the nozzle 5 via the orifice 5a impinges totally on the hot area ABCD of the preform 3. There is no cold area.

Figure 5 is a diagrammatic representation of the components of the system shown in figure 1 in a position that is optimized in accordance with the invention in the case of rightward translatory movement of the preform 3 relative to the nozzle 5

and the torch 4. The axis of the nozzle 5 is at a distance  $d$  from the axis of the torch 4 equal to the distance  $d$  shown in figure 4 and on its downstream side relative to the direction of translatory movement of the preform 3 relative to the torch 4.

Consequently the cone 14 of deposition of the gases or particles leaving the nozzle 5

5 via the orifice 5a impinges totally on the hot area ABCD of the preform 3. There is no cold area. More generally, the heating means are not cylindrically symmetrical.

The axis of the nozzle 5 is at a distance  $d'$ , which is not equal to the distance  $d$  shown in figure 4, from the axis of the torch 4, on its downstream side relative to the direction of translatory movement of the preform 3 relative to the torch 4.

10 The foregoing description relates to the situation in which relative movement of the heating means in the form of the torch 4 and the injector means in the form of the nozzle 5 is obtained by moving the injector means relative to the heating means. Of course, it is equally possible in the context of the invention for the heating means to move relative to the injector means, with substantially the same result.

15 Of course, the method of the invention is not limited to the representations described above. In particular, it can be used for plasma surfacing processes and also for other surfacing processes such as the OVD process.

THERE IS CLAIMED:

1. A method of fabricating an optical fiber preform including a step of outside deposition of silica possibly doped with at least one dopant by injecting at least one substance in the form of silica or a precursor of silica in the vicinity of a heating area created by heating means during at least one pass of injector means and said heating means along a longitudinal axis of said preform during which the relative positions of said injector means and said heating means are adjusted so that said silica is deposited in said heated area regardless of the position of said heating means.
2. The method claimed in claim 1 wherein said adjustment is carried out between each pass and the next.
3. The method claimed in claim 1 wherein said heating means have a main axis in a plane substantially perpendicular to said longitudinal axis of said preform, said injector means have a main axis at a fixed angle to said main axis of said heating means in a plane substantially perpendicular to said longitudinal axis of said preform and said injector means and said heating means move relative to each other in a direction parallel to said longitudinal axis of said preform.

FIG. 1

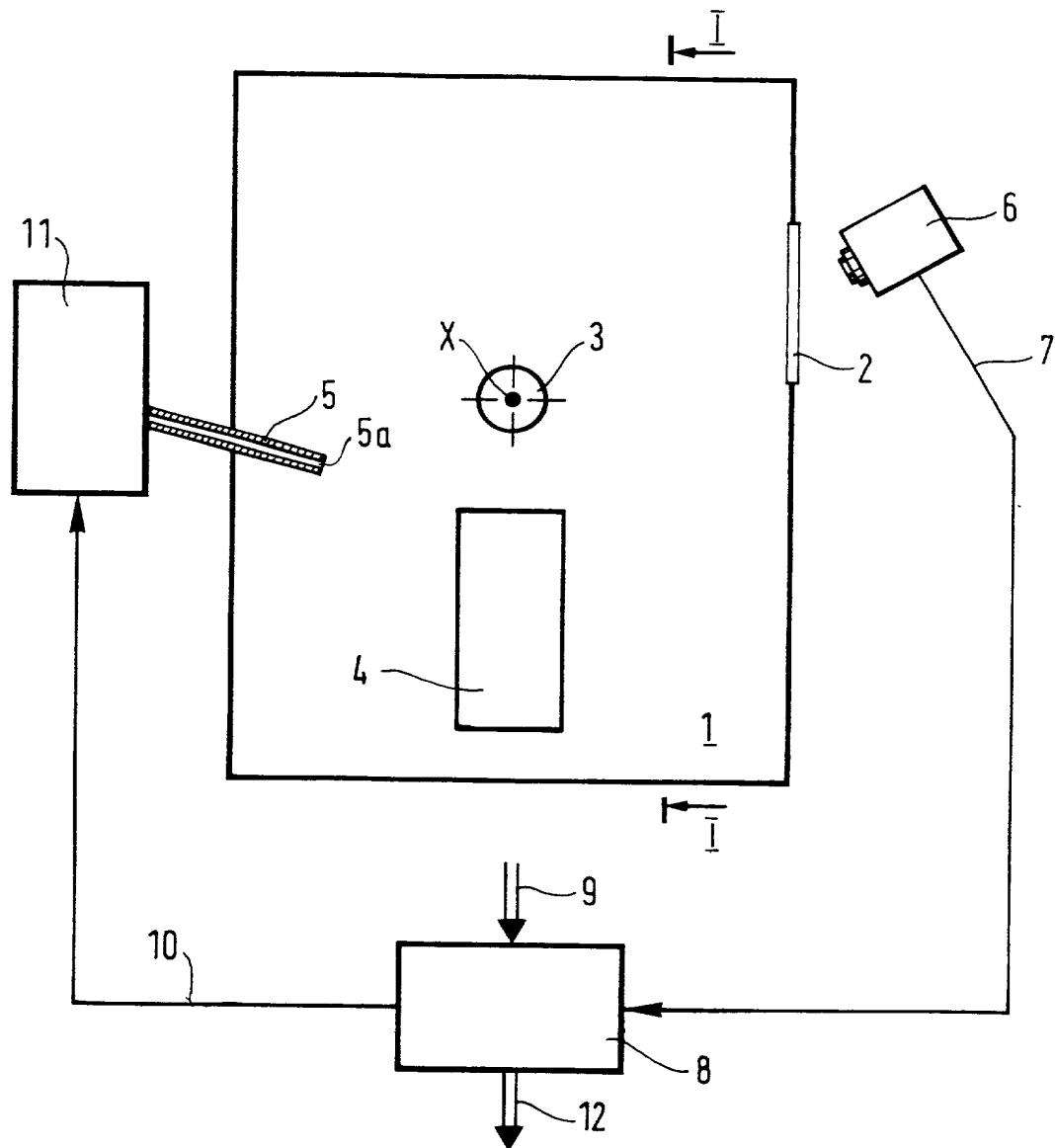


FIG. 2

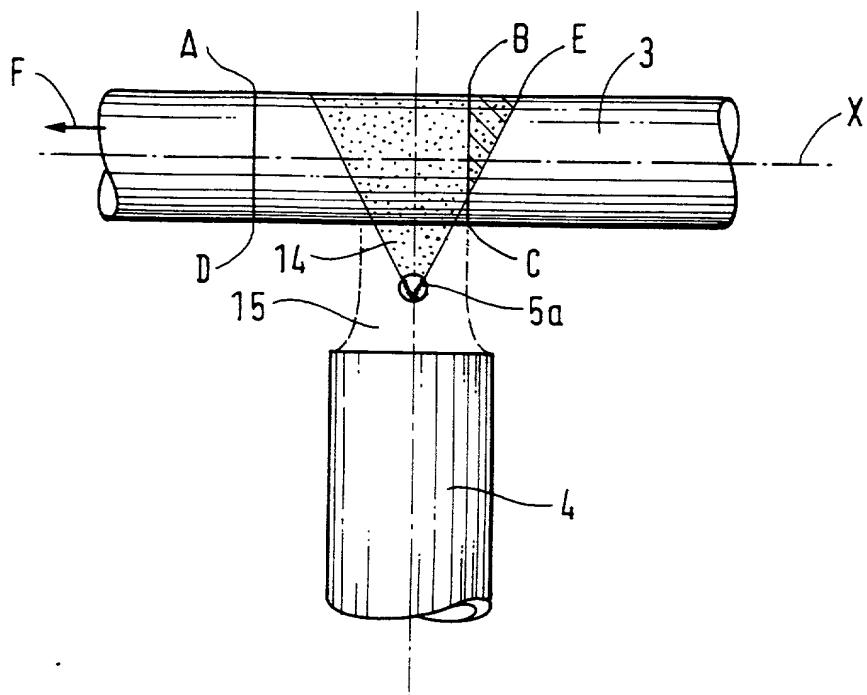


FIG. 3

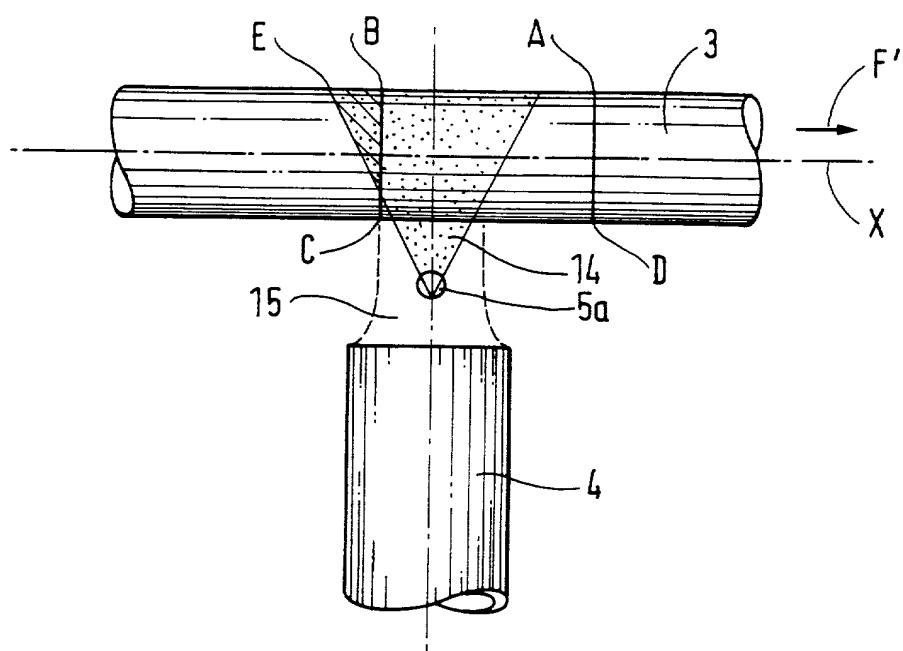


FIG. 4

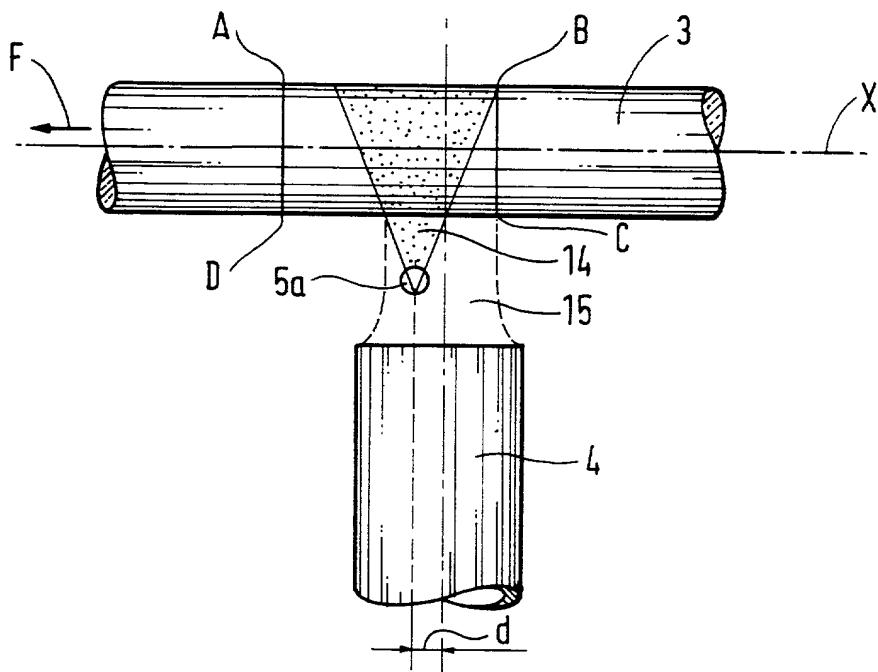
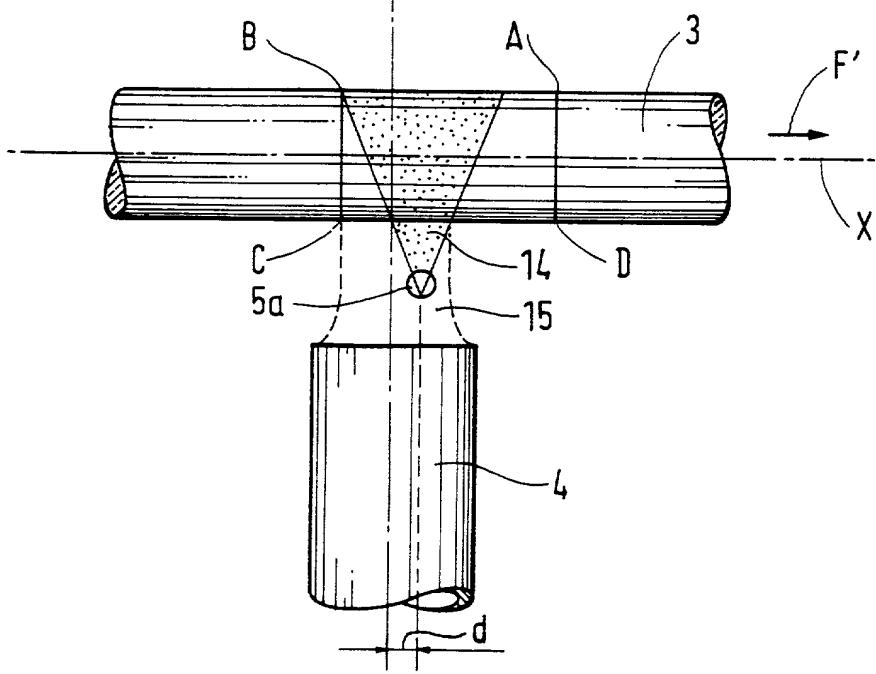


FIG. 5



# French Language Declaration

## Declaration and Power of Attorney for Patent Application

### Déclaration et Pouvoirs pour Demande de Brevet

#### French Language Declaration

En tant que l'inventeur nommé ci-après, je déclare par le présent acte que:

Mon domicile, mon adresse postale et ma nationalité sont ceux figurant ci-dessous à côté de mon nom.

Je crois être le premier inventeur original et unique (si un seul nom est mentionné ci-dessous), ou l'un des premiers co-inventeurs originaux (si plusieurs noms sont mentionnés ci-dessous) de l'objet revendiqué, pour lequel une demande de brevet a été déposée concernant l'invention de la description identifiée par le numéro de référence

As a below named inventor, I hereby declare that:

My residence, post office address and citizenship are as stated next to my name.

I believe I am the original, first and sole inventor (if only one name is listed below) or an original, first and joint inventor (if plural names are listed below) of the subject matter which is claimed and for which a patent is sought on the invention in the specification identified by Docket No.

**101795/CD/TEL**

Je déclare par le présent acte avoir passé en revue et compris le contenu de la description ci-dessus, revendications comprises.

Je reconnais devoir divulguer toute information pertinente à la brevetabilité, comme défini dans le Titre 37, § 1.56 du Code fédéral des réglementations.

Je revendique par le présent acte avoir la priorité étrangère, en vertu du Titre 35, § 119(a)-(d) ou § 365(b) du Code des Etats-Unis, sur toute demande étrangère de brevet ou certificat d'inventeur ou, en vertu du Titre 35, § 365(a) du même Code, sur toute demande internationale PCT désignant au moins un pays autre que les Etats-Unis et figurant ci-dessous et, j'ai aussi indiqué ci-dessous toute demande étrangère de brevet, tout certificat d'inventeur ou toute demande internationale PCT ayant une date de dépôt précédant celle de la demande à propos de laquelle une priorité est revendiquée.

I hereby state that I have reviewed and understand the contents of the above identified specification, including the claims.

I acknowledge the duty to disclose information which is material to patentability as defined in Title 37, Code of Federal Regulations, § 1.56.

I hereby claim foreign priority under Title 35, United States Code, § 119(a)-(d) or § 365(b) of any foreign application(s) for patent or inventor's certificate, or § 365(a) of any PCT International application which designated at least one country other than the United States, listed below, and have also identified below any foreign application for patent or inventor's certificate, or PCT International application having a filing date before that of the application on which priority is claimed.

Prior foreign application(s) for which priority is claimed

Demande(s) de brevet étrangère(s) antérieure(s) dont la priorité est revendiquée

(Number) (Numéro)	(Country) (Pays)	(Day/Month/Year Filed) (Jour/Mois/Année de dépôt)
99 02 815	FRENCH	08 MARCH 1999

Prior foreign applications for which priority is not claimed

Demande(s) de brevet étrangères antérieure(s) dont la priorité n'est pas revendiquée

(Number) (Numéro)	(Country) (Pays)	(Day/Month/Year Filed) (Jour/Mois/Année de dépôt)

## French Language Declaration

Je revendique par le présent acte tout bénéfice, en vertu du Titre 35, § 119(e) du Code des Etats-Unis, de toute demande de brevet provisoire effectuée aux Etats-Unis et figurant ci-dessous.

I hereby claim the benefit under Title 35, United States Code, § 119(e) of any United States provisional application(s) listed below.

---

(Application No.)  
(No de demande)

---

(Filing Date)  
(Date de dépôt)

Je revendique par le présent acte tout bénéfice, en vertu du Titre 35, § 120 du Code des Etats-Unis, de toute demande de brevet effectuée aux Etats-Unis, ou en vertu du Titre 35, § 365(c) du même Code, de toute demande internationale PCT désignant les Etats-Unis et figurant ci-dessous et, dans la mesure où l'objet de chacune des revendications de cette demande de brevet n'est pas divulgué dans la demande antérieure américaine ou internationale PCT, en vertu des dispositions du premier paragraphe du Titre 35, § 112 du Code des Etats-Unis, je reconnais devoir divulguer toute information pertinente à la brevetabilité, comme défini dans le Titre 37, § 1.56 du Code fédéral des réglementations, dont j'ai pu disposer entre la date de dépôt de la demande antérieure et la date de dépôt de la demande nationale ou internationale PCT de la présente demande.

I hereby claim the benefit under Title 35, United States Code, § 120 of any United States application(s), or § 365(c) of any PCT International application designating the United States, listed below and, insofar as the subject matter of each of the claims of this application is not disclosed in the prior United States or PCT International application in the manner provided by the first paragraph of Title 35, United States Code, § 112, I acknowledge the duty to disclose information which is material to patentability as defined in Title 37, Code of Federal Regulations, § 1.56 which became available between the filing date of the prior application and the national or PCT International filing date of this application.

---

(Application No.)  
(No de demande)

---

(Filing Date)  
(Date de dépôt)

---

(Status)(patented, pending, abandoned)  
(Statut)(breveté, en cours d'examen, abandonné)

Je déclare par le présent acte que toute déclaration ci-incluse est, à ma connaissance, véridique et que toute déclaration formulée à partir de renseignements ou de suppositions est tenue pour véridique; et de plus, que toutes ces déclarations ont été formulées en sachant que toute fausse déclaration volontaire ou son équivalent est passible d'une amende ou d'une incarcération, ou des deux, en vertu de la Section 1001 du Titre 18 du Code des Etats-Unis, et que de telles déclarations volontairement fausses risquent de compromettre la validité de la demande de brevet ou du brevet délivré à partir de celle-ci.

I hereby declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issued thereon.

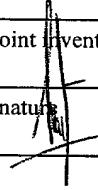
# French Language Declaration

**POUVOIRS:** En tant que l'inventeur cité, je désigne par la présente l'(les) avocat(s) et/ou agent(s) suivant(s) pour qu'ils poursuive(nt) la procédure de cette demande de brevet et traite(nt) toute affaire s'y rapportant avec l'Office des brevets et des marques: (mentionner le nom et le numéro d'enregistrement).

John H. Mion, Reg. No. 18,879; Thomas J. Macpeak, Reg. No. 19,292; Robert J. Seas, Jr., Reg. No. 21,092; Darryl Mexic, Reg. No. 23,063; Robert V. Sloan, Reg. No. 22,775; Peter D. Olexy, Reg. No. 24,513; J. Frank Osha, Reg. No. 24,625; Waddell A. Biggart, Reg. No. 24,861; Louis Gubinsky, Reg. No. 24,835; Neil B. Siegel, Reg. No. 25,200; David J. Cushing, Reg. No. 28,703; John R. Inge, Reg. No. 26,916; Joseph J. Ruch, Jr., Reg. No. 26,577; Sheldon I. Landsman, Reg. No. 25,430; Richard C. Turner, Reg. No. 29,710; Howard L. Bernstein, Reg. No. 25,665; Alan J. Kasper, Reg. No. 25,426; Kenneth J. Burchfiel, Reg. No. 31,333; Gordon Kit, Reg. No. 30,764; Susan J. Mack, Reg. No. 30,951; Frank L. Bernstein, Reg. No. 31,484; Mark Boland, Reg. No. 32,197; William H. Mandir, Reg. No. 32,156; Scott M. Daniels, Reg. No. 32,562; Brian W. Hannon, Reg. No. 32,778; Abraham J. Rosner, Reg. No. 33,276; Bruce E. Kramer, Reg. No. 33,725; Paul F. Neils, Reg. No. 33,102; and Brett S. Sylvester, Reg. No. 32,765; and Robert M. Masters, Reg. No. 35,603.

Adresser toute correspondance à:

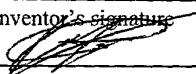
Send Correspondence to:  
SUGHRUE, MION, ZINN, MACPEAK & SEAS, PLLC  
2100 Pennsylvania Avenue, N.W., Suite 800  
Washington, D.C. 20037-3213

Nom complet de l'unique ou premier inventeur	Full name of sole or first inventor (First Middle Last) Pierre RIPOCHE	
Signature de l'inventeur	Date	Inventor's signature  13-12-99 Date
Domicile	Residence 45300 PITHIVIERS FRANCE	
Nationalité	Citizenship French	
Adresse postale	Post Office Address 2, Avenue Marcel Denon 45300 PITHIVIERS FRANCE	
Nom complet du second co-inventeur, le cas échéant	Full name of second joint inventor, if any (First Middle Last) Alain DROUART	
Signature du second inventeur	Date	Second inventor's signature  13-12-99 Date
Domicile	Residence 92000 NANTERRE FRANCE	
Nationalité	Citizenship French	
Adresse postale	Post Office Address 2 avenue Félix Faure 92000 NANTERRE FRANCE	

(Fournir les mêmes renseignements et la signature de tout co-inventeur supplémentaire.)

(Supply similar information and signature for third and subsequent joint inventors.)

## French Language Declaration

Nom complet du troisième co-inventeur, le cas échéant		Full name of third joint inventor, if any (First Middle Last) Benoît GOUEZ	
Signature du troisième l'inventeur	Date	Third inventor's signature 	Date 13/12/93
Domicile	Residence 78260 ACHERES France		
Nationalité	Citizenship French		
Adresse postale	Post Office Address 17 Place du 14 Juillet 78260 ACHERES FRANCE		
Nom complet du quatrième co-inventeur, le cas échéant		Full name of fourth joint inventor, if any (First Middle Last)	
Signature du quatrième l'inventeur	Date	Fourth inventor's signature	Date
Domicile	Residence		
Nationalité	Citizenship		
Adresse postale	Post Office Address		
Nom complet du cinquième co-inventeur, le cas échéant		Full name of fifth joint inventor, if any (First Middle Last)	
Signature du cinquième l'inventeur	Date	Fifth inventor's signature	Date
Domicile	Residence		
Nationalité	Citizenship		
Adresse postale	Post Office Address		
Nom complet du sixième co-inventeur, le cas échéant		Full name of sixth joint inventor, if any (First Middle Last)	
Signature du sixième l'inventeur	Date	Sixth inventor's signature	Date
Domicile	Residence		
Nationalité	Citizenship		
Adresse postale	Post Office Address		